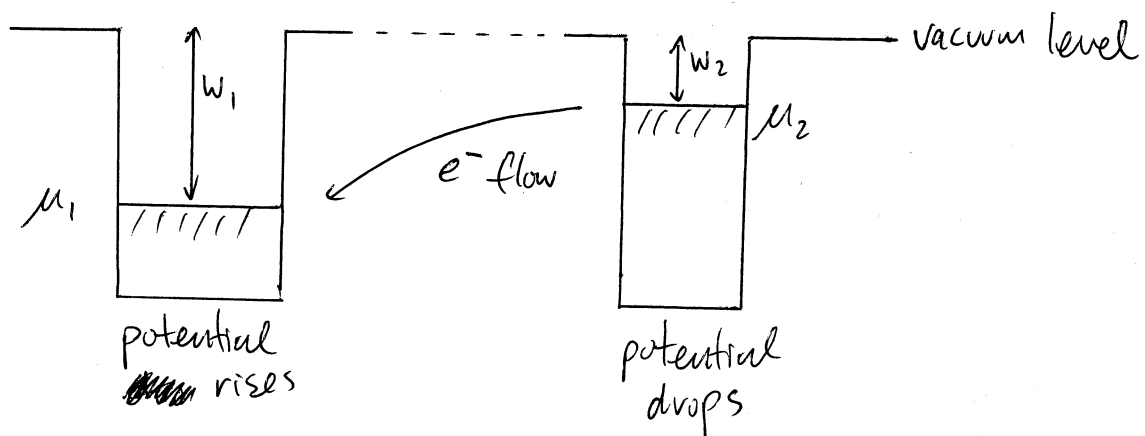


\* Two conductors brought into contact

→ electrons flow from material of higher  $\mu$  to lower  $\mu$

→ each material experiences a change in net charge and hence a change in electrostatic potential relative to the vacuum level



→ number of electrons transferred is tiny; no observable effect on band filling

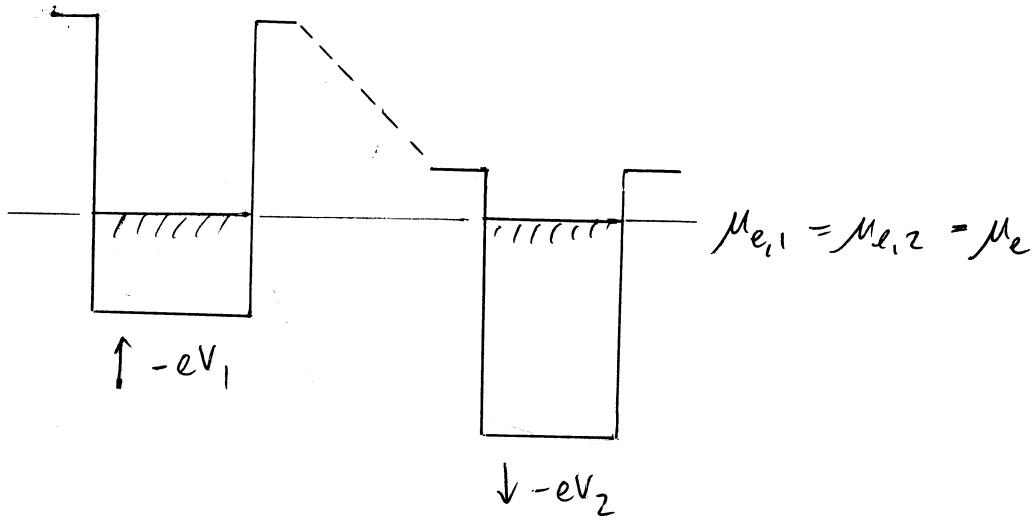
→ equilibrium reached when the electrochemical potential  $\mu_e = \mu - eV$  comes into alignment

i.e. 
$$\mu_1 - eV_1 = \mu_2 - eV_2$$

or contact potential 
$$V_2 - V_1 = (\mu_2 - \mu_1) / e$$

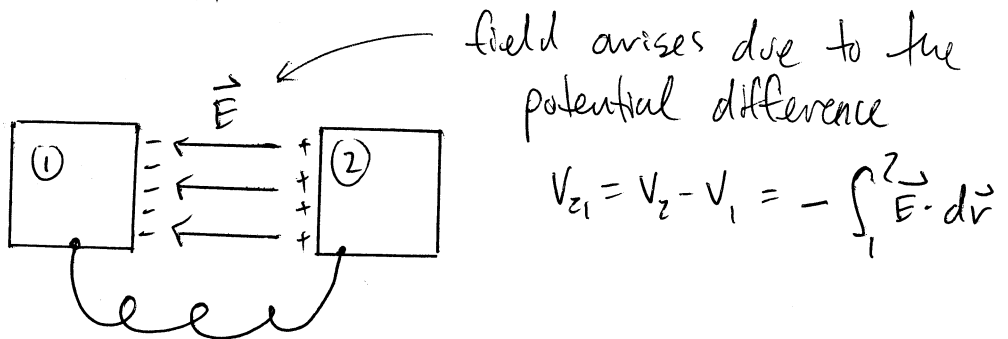
→ related to work functions by

$$V_{21} = V_2 - V_1 = (w_1 - w_2) / e$$

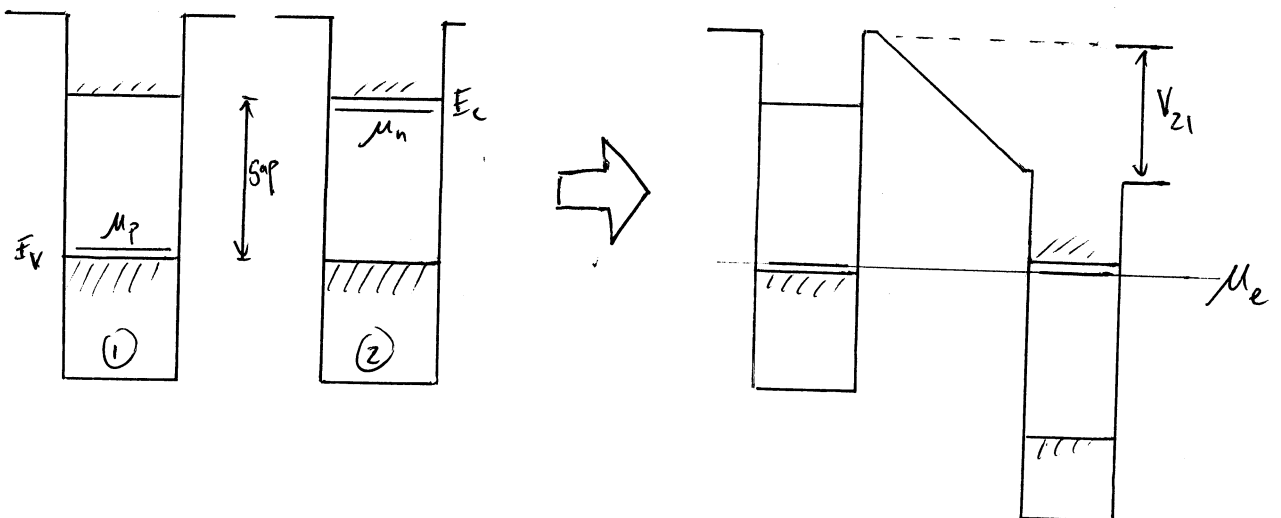


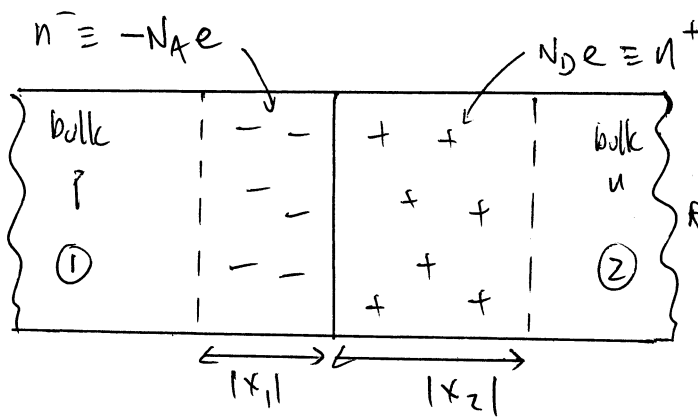
→ probability of occupancy for any level  $\epsilon$  is  $\frac{1}{1 + e^{\beta(\epsilon - \mu_e)}}$

→ transferred charge generally resides on surfaces to minimize the energy



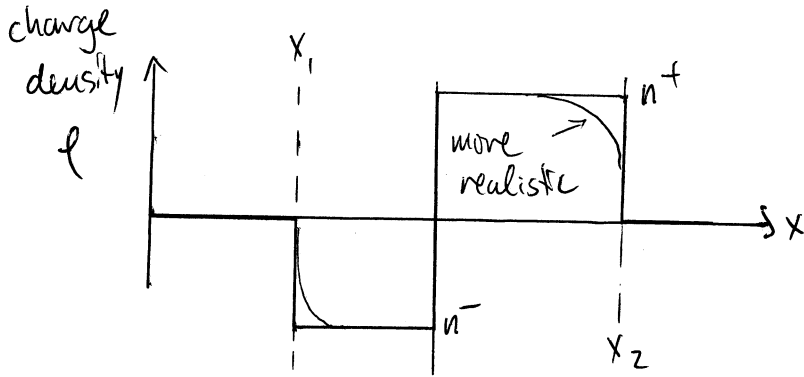
\* p-type and n-type semiconductor brought into contact





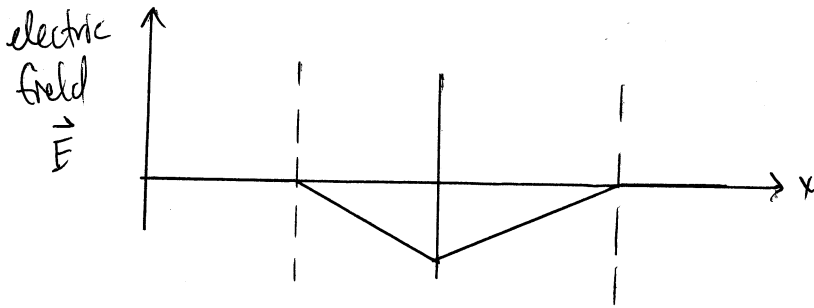
→ charge equality:  $n^- x_1 = n^+ x_2$   
 or  $N_A |x_1| = N_D |x_2|$

→ cross-sectional area  $A$  in  $y, z$  coordinates



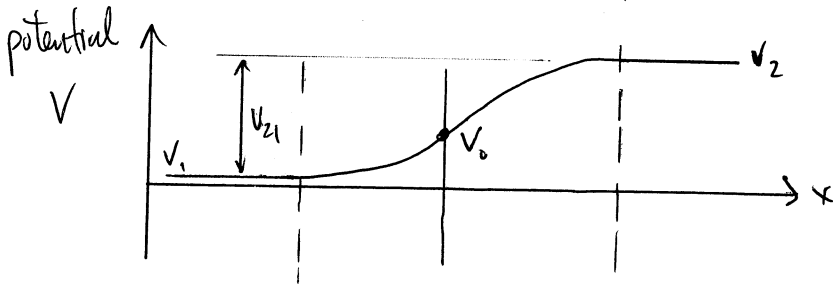
→ linear electric field pointing from n-type to p-type region

$$EA = \frac{Q}{\epsilon} = -\frac{N_A e}{\epsilon} A (x - x_1)$$



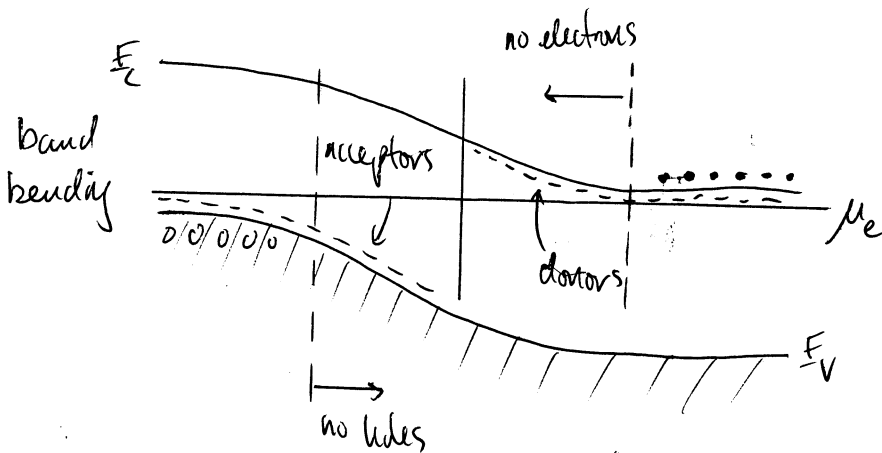
$$V_0 - V_1 = \int_1^0 dV = \int_{x_1}^0 E dx$$

$$= \frac{N_A e}{\epsilon} \int_{x_1}^0 (x - x_1) dx$$



$$EA = \frac{Q}{\epsilon} = N_D e A (x - x_2)$$

$$V_2 - V_0 = \frac{1}{2} \frac{N_D e}{\epsilon} x_2^2$$



$$V_2 - V_1 = \frac{e}{2\epsilon} [N_A x_1^2 + N_D x_2^2]$$

\* Contact potential  $V_{21} = \frac{W_1 - W_2}{e} = \frac{W_p - W_n}{e} \approx 1 \text{ volt}$ ,

so actual values of  $x_1, x_2$  are highly constrained

→ e.g. ~~dielectric~~  $N_A \sim N_D \sim 10^{18} \text{ cm}^{-3}$

dielectric  $\epsilon \sim 10$

contact potential  $V_{21} \sim 1 \text{ volt}$

then  $|x_1| \sim |x_2| \sim 1000 \text{ \AA}$

→ on the other hand, for two metals

$n^+ \sim n^- \sim 10^{22} \text{ cm}^{-3}$

$\epsilon \sim 1$

then  $|x_1| \sim |x_2| \lesssim 1 \text{ \AA}$  no meaningful depletion region

↑  
less than a lattice spacing

\* Classical diffusion (Einstein)

→ particle current  $\vec{J} = -D \vec{\nabla} n$  flows "downhill" along the density gradient

→ for Boltzmann occupation,  $n \sim \sum_k e^{-(\epsilon_k - \mu)/k_B T}$

and  $\vec{\nabla} n = \vec{\nabla} \mu \cdot \frac{n}{k_B T}$

→ corresponding charge current is

$$\vec{J} = (-e) \left( -\frac{D}{k_B T} \right) n \vec{\nabla} \mu = \frac{e D n}{k_B T} \vec{\nabla} \mu \equiv \frac{\sigma}{e} \vec{\nabla} \mu$$

conductivity

→ Einstein relation

$$D = \frac{\sigma \cdot k_B T}{n e^2} \equiv \frac{\mu_0 k_B T}{e}$$

"mobility":  $\sigma = n e \mu_0$

\* Ohm's law in the material context

$$\vec{J} = \frac{\sigma}{e} \nabla \mu_e \leftarrow \text{follows the electrochemical potential}$$

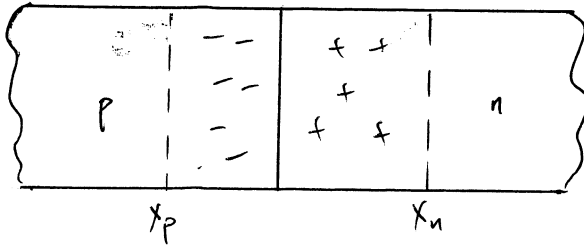
$$= \frac{\sigma}{e} \nabla \mu - \sigma \nabla V$$

$$= \frac{\sigma}{e} \nabla \mu + \sigma \vec{E}$$

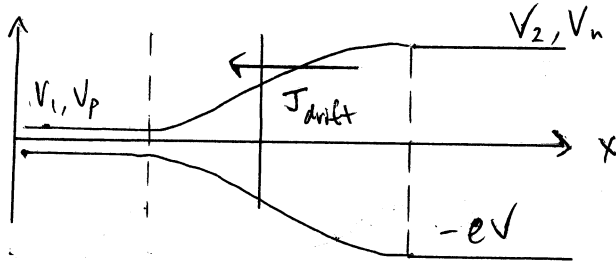
↑ diffusion current

↑ drift current

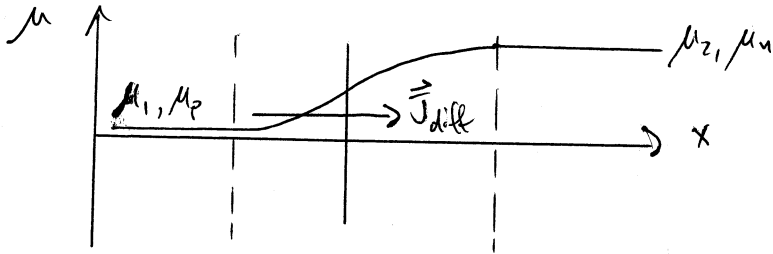
\* Drift and diffusion currents in the p-n junction



→  $\mu_e = \mu - eV$  constant across the sample



$$\vec{J}_{drift} = -\sigma \vec{\nabla} V$$

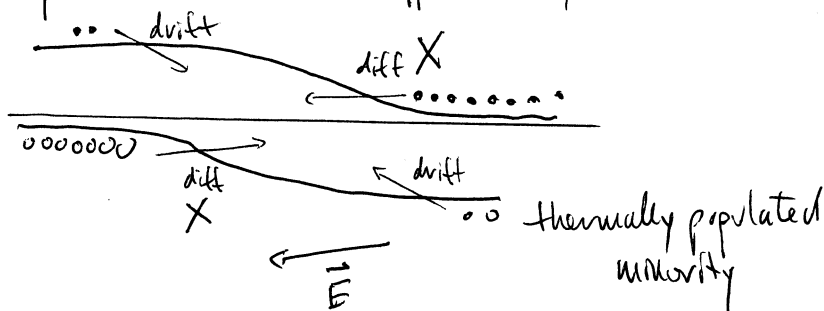


$$\vec{J}_{diff} = \frac{\sigma}{e} \vec{\nabla} \mu$$

→ no net current since  $\vec{J}_{drift}$  and  $\vec{J}_{diff}$  are equal and opposite

→ minority carriers swept along by electric field

→ majority carriers penetrate adjacent region by population pressure but are opposed by the  $\vec{E}$  field



# \* Rectification by a p-n junction

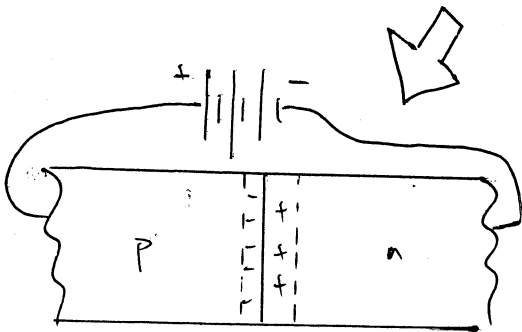
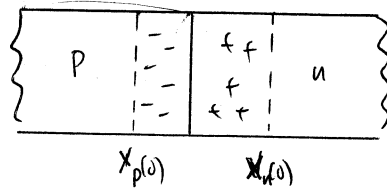
→ recall

$$x_{n,p} = \pm \left[ \frac{\epsilon (N_A/N_D)^{\pm 1} V_{i2}}{e^2 (N_A + N_D)} \right]^{1/2}$$

→ leave the analysis the same except for the addition of an external potential  $V_{ext}$

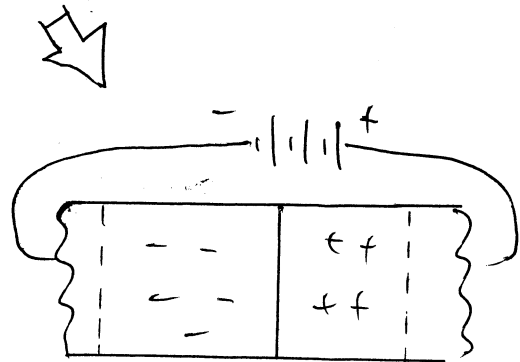
red. put  $V_{i2} \rightarrow V_{i2} - V_{ext}$

$$x_{n,p}(V_{ext}) = x_{n,p}(0) \left( 1 - \frac{V_{ext}}{V_{i2}} \right)^{1/2}$$



~~reverse~~ forward bias

$$V_{ext} > 0$$



reverse bias

$$V_{ext} < 0$$

→ composition of the total current

$$J_{\text{hole, recombination}} = C_h \cdot e^{\beta V_{\text{ext}}}$$

→  
majority holes must be thermally excited over the barrier  $V_{z1} - V_{\text{ext}}$

$$J_{\text{hole, generation}} = C_h \cdot 1$$

←  
minority holes wander into the depletion region and are swept along by the  $\vec{E}$  field

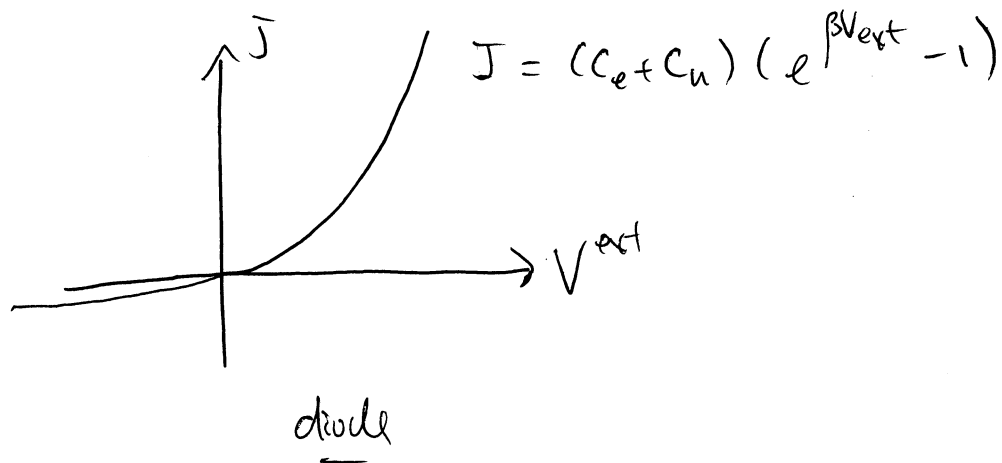
$$J_{\text{electron, generation}} = C_e \cdot 1$$

→  
minority electrons

$$J_{\text{electron, recombination}} = C_e \cdot e^{\beta V_{\text{ext}}}$$

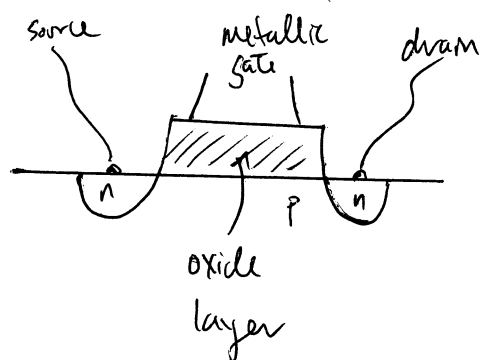
←  
majority electrons

\* Net current is asymmetric in the applied voltage





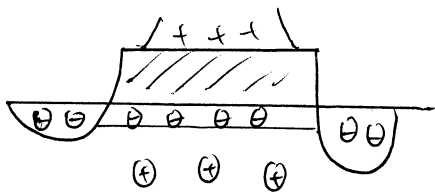
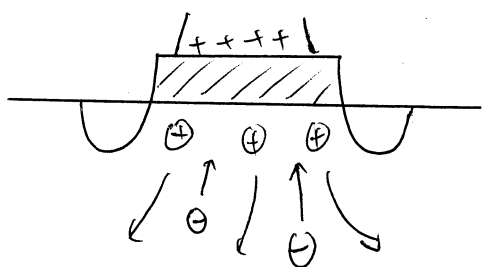
# \* Metal Oxide Semiconductor Field Effect Transistor (MOSFET)



→ variable mode of operation depending on whether a voltage is applied to the gate

① in the absence of a gate voltage, there is a large barrier to current flow from source to drain

② if the gate voltage is turned up, positive charge will pile up against the oxide:



as a result nearby holes in the p-type region are repelled and electrons attracted

~~as a result~~ an "inversion layer" with majority electron carriers is established that connects source to drain

→ hence, the gate acts as a switch that turns on or off the current flow through the device

→ band bending picture

